## **AMENDMENTS TO THE CLAIMS**

- 1-21. (Canceled)
- 22. (Currently Amended) A method comprising:

receiving a photoelectrically induced signal in an array of photoreceptors on a semiconductor substrate;

controlling each photoreceptor in the array of photoreceptors to simultaneously initiate a common integration period;

at the end of each integration period, controlling each photoreceptor in the array of photoreceptors to transfer its photoelectrically induced signal to a respective separated storage node located within a semiconductor well region formed in the semiconductor substrate; and

preventing said-separated storage node from integrating charge, wherein

the storage node is doped to a first conductivity type and

a portion of the semiconductor well surrounding the storage node is

doped to a second conductivity type.

- 23. (Canceled)
- 24. (Currently amended) A method as in claim 22, wherein said preventing comprises shielding said-separated storage node with a light shield overlying at least said-separated storage node.

Docket No.: M4065.0841/P841-A

25. (Currently amended) A method as in claim 22, wherein said preventing comprises shielding said-separate semiconductor well with a light shield overlying said semiconductor well.

## 26. (Canceled)

- 27. (Original) A method as in claim 25, further comprising enabling a first reset operation which resets a value of said storage node, and enabling a second reset operation, which resets a value of said photoreceptor.
- 28. (Previously presented) A method as in claim 27, wherein said first and second reset operations each comprises activating a gate within said semiconductor well.
- 29. (Previously presented) A method as in claim 28, wherein said photoelectrically induced signal is a signal indicative of charge produced by said photoreceptor during said integration period.
- 30. (Original) A method as in claim 28, wherein said photoreceptor includes a photodiode.
- 31. (Original) A method as in claim 28, wherein said photoreceptor includes a photogate.
- 32. (Previously presented) A method as in claim 25, further comprising preventing said photoreceptor from acquiring a photoelectrically induced signal which is greater than a pre-determined amount.

Docket No.: M4065.0841/P841-A

33. (Currently amended) A method as in claim 25, further comprising forming a second-separated semiconductor well for each of the plurality of photoreceptors in the array.

34-52. (Canceled)

53. (Previously presented) A method comprising:

forming a photosensor in a substrate, the photosensor for forming charges in response to applied light;

forming a first well region in the substrate, the first well region being separated from the photosensor and being doped to a first conductivity type;

forming a storage region located in the first well region, the storage region for collecting charge generated by the photosensor and being doped to a second conductivity type; and

shielding at least a portion of the storage region by forming a shielding layer over the storage region.

- 54. (Previously presented) The method of claim 53, wherein the storage region comprises a p-type region and the first well region comprises an n-well.
- 55. (Previously presented) The method of claim 53, further comprising the act of forming a second well region such that said photosensor is located within said second well region.
- 56. (Previously presented) The method of claim 55, wherein said first and said second well regions are n-well regions.

Application No. 10/623,533 Reply to Office Action of March 13, 2006 Docket No.: M4065.0841/P841-A

57. (Previously presented) The method of claim 53, wherein the act of shielding at least a portion of the storage region comprises forming a metal light shield layer over the first well region.

58. (Previously presented) The method of claim 53, wherein the act of forming a photosensor comprises one of forming a photodiode and forming a photogate.